

## Claims

[c1] 1. A metal-oxide-semiconductor (MOS) device for an electrostatic discharge (ESD) protection circuit with the MOS device serving as a clamping device in the ESD protection circuit, comprising:

- a first conductive type substrate;
- a gate structure, disposed over the substrate;
- a second conductive type source region and a second conductive type source region, separately disposed in the substrate on each side of the gate structure;
- a second conductive type doped layer, disposed in the substrate underneath the source region and the drain region but apart from the source region and the drain region; and
- a second conductive type extended doped region, disposed in the substrate adjacent to the doped layer and the source region;

wherein the drain region, the substrate and the source region together form a first parasitic bipolar junction (BJT) and the drain region, the substrate and the doped layer together form a second parasitic bipolar junction transistor so that a current flowing into the drain region is channeled to a common voltage terminal via the first

parasitic BJT and the second parasitic BJT.

- [c2] 2. The MOS device of claim 1, wherein the substrate, the gate structure, the source region and the extended doped region are coupled to the common voltage terminal.
- [c3] 3. The MOS device of claim 1, wherein the first conductive type is a p-doped material and the second conductive type is an n-doped material.
- [c4] 4. The MOS device of claim 1, wherein the first conductive type is an n-doped material and the second conductive type is a p-doped material.
- [c5] 5. The MOS device of claim 1, wherein the gate structure comprises a bottom gate dielectric layer and a top gate conductive layer.
- [c6] 6. A metal-oxide-semiconductor (MOS) device for an electrostatic discharge (ESD) protection circuit with the MOS device serving as a clamping device, comprising:
  - a first conductive type substrate;
  - a plurality of parallel-connected transistors, disposed on the substrate with each transistor having:
    - a gate structure disposed over the substrate;
    - a second conductive type source region and a second conductive type drain region, separately disposed in the

substrate on each side of the gate structure; a second conductive type doped layer, disposed in the substrate underneath the transistors but apart from the source regions and the drain regions; and a second conductive type extended doped region, disposed in the substrate adjacent to the doped layer and the source region of the outmost transistors among the parallel-connected transistors; wherein the drain region, the substrate and the source region of various transistors form at least a first parasitic bipolar junction transistor and the drain region, the substrate and the doped layer of various transistor at least form a second parasitic bipolar junction transistor so that currents flowing into various drain region of the transistors are channeled to a common voltage terminal via the first parasitic bipolar junction transistor and the second parasitic bipolar junction transistor.

- [c7] 7. The MOS device of claim 6, wherein the substrate and the gate structure, the source region, the extended doped region of the transistors are coupled to the common voltage terminal.
- [c8] 8. The MOS device of claim 6, wherein the first conductive type is a p-doped material and the second conductive type is an n-doped material.

- [c9] 9. The MOS device of claim 6, wherein the first conductive type is an n-doped material and the second conductive type is a p-doped material.
- [c10] 10. The MOS device of claim 6, wherein the gate structure comprises a bottom gate dielectric layer and a top gate conductive layer.
- [c11] 11. The MOS device of claim 6, wherein every adjacent pair of transistors either uses a common source region or a common drain region.